

Self-textured ZnO *via* AACVD of alkyl alkoxides: A solution-based seed-less route towards optoelectronic-grade coatings.

SUPPORTING INFORMATION

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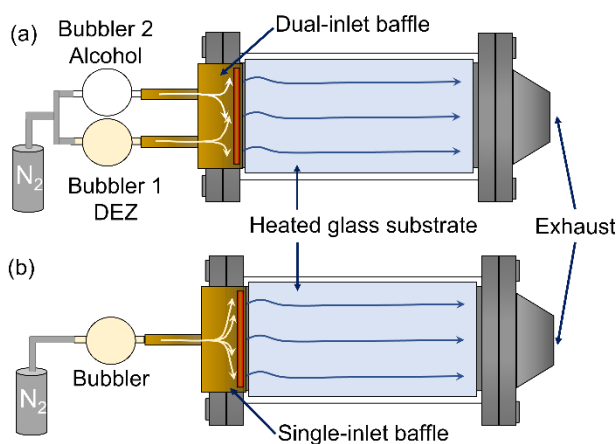


Figure S1. Schematic top-view representation of a (a) double-source and a (b) single-source AACVD configuration, both containing a blade element on the baffle to generate a laminar flow inside the reactor (blue arrows).

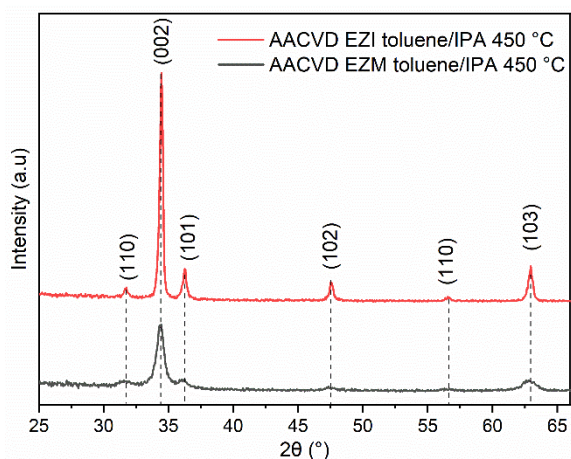


Figure S2. GIXRD patterns of ZnO thin films grown from EZI (top red) and EZI (bottom black) in toluene/isopropanol anhydrous solutions at 450 °C using a single-inlet AACVD configuration.

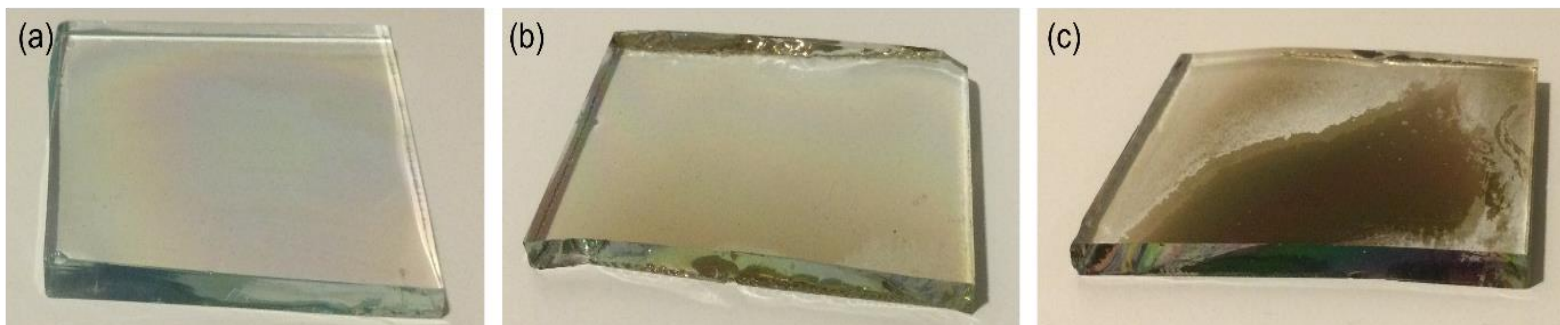


Figure S3. Picture of sections of ZnO thin film grown *via* AACVD of Zn(acac)₂ in MeOH at (a) 400 °C, (b) 450 °C and (c) 500 °C exhibiting increasing carbon contamination.

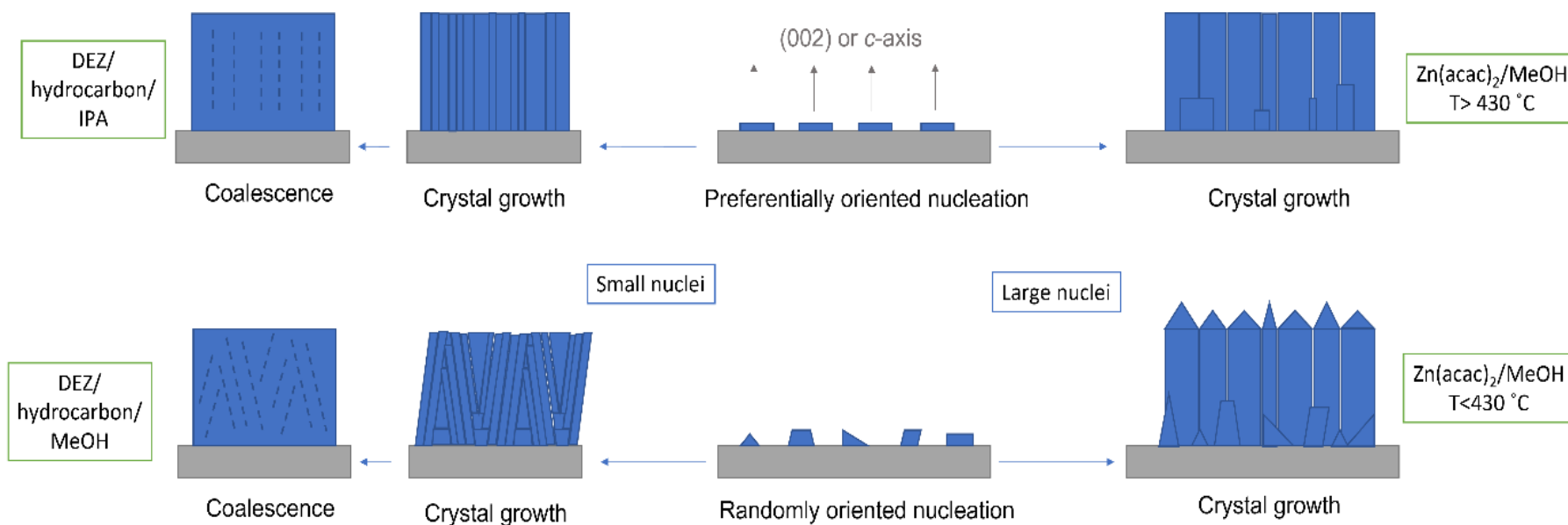


Figure S4. Schematic representation of nucleation, crystal growth and texture evolution during polycrystalline ZnO film deposition using AACVD of Zn(acac)₂ and DEZ solutions.

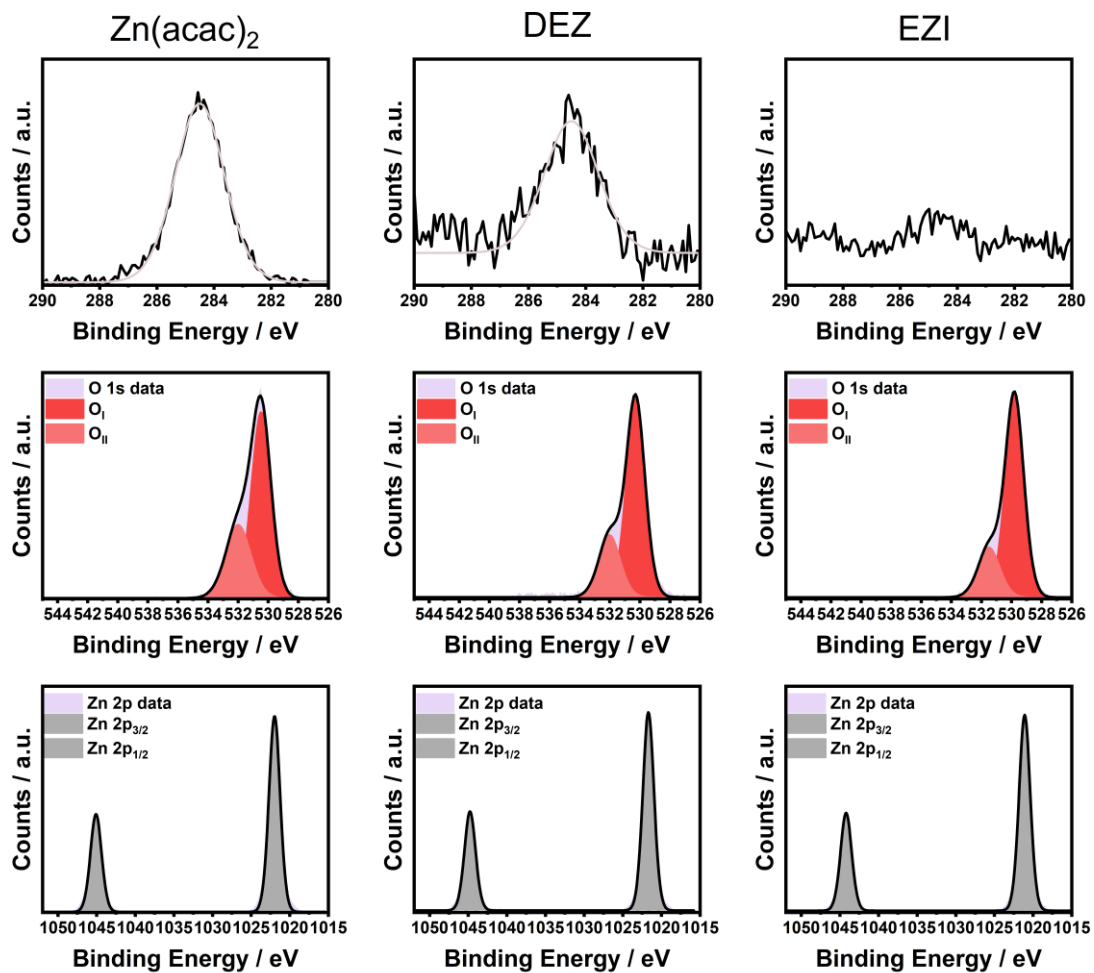


Figure S5. Schematic representation of nucleation, crystal growth and texture evolution during polycrystalline ZnO film deposition using AACVD of Zn(acac)₂ and DEZ solutions.